

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 09/653,156
Filing Date August 31, 2000
Inventor Vishnu K. Agarwal et al.
Assignee Micron Technology, Inc.
Group Art Unit 2813
Examiner Thanh T. Nguyen
Attorney's Docket No. MI22-1518
Title: Enhanced Surface Area Capacitor Fabrication Methods

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT
References – See Attached Form PTO-1449

In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449. No admission is made regarding whether all the submitted references are prior art.


This Supplemental Information Disclosure Statement is being filed after the filing of the Request for Continued Examination (RCE) Application and before receipt of the first Office Action. Therefore, no fee is believed to be required. However, in the event that a fee is required for filing this Supplemental Information Disclosure Statement, please charge the fee specified under 37 C.F.R. §1.17(p) to Deposit Account No. 23-0925. Please credit Deposit Account No. 23-0925 with any overpayment of the above fee.

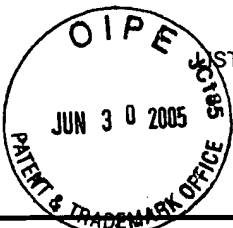
Citation of these references is respectfully requested.

Dated: 30 Jun 2005

By: _____

Respectfully submitted,


James E. Lake
Reg. No. 44,854

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1518	SERIAL NO. 09/653,156			
				APPLICANT: Vishnu K. Agarwal et al.				
				FILING DATE August 31, 2000	GROUP 2813			
U.S. PATENT DOCUMENTS								
*Examiner's Initials	AA	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	6,359,295 B2	03/2002	Yang et al.				
	AB	6,403,156	06/2002	Jang				
	AC	6,596,602 B2	07/2003	Lizuka et al.				
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	AE	6,664,186 B1	12/2003	Callegari et al.				
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	AH	2002/0142488	10/2002	Hong, Suk-Kyoung				
	AI	2002/0109198 A1	08/2002	Yang et al.				
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AJ	KR 2002046433	05/2003	Lee, J.W.				
	AK	EP 1 508 906 A2	02/2005	Lee et al.				
	AL							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AM		Ritala et al.; <i>Perfectly Conformal TiN and Al2O3 Films Deposited by Atomic Layer Deposition</i> ; Chemical Vapor Deposition, v. 5, No. 1, 1999, pp. 7-9.					
	AN							
	AO							
EXAMINER		DATE CONSIDERED						
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>								

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